

	Hit s	Search Text	DBs
28	29	(illumination or light or radiation) and ((optic\$4 or project\$4 or object\$4) same lens\$4) and ((mask or reticle or photomask) same (mount or stage or hold\$4)) and (substrate or workpiece) and ((mask or reticle or photomask) same (slit\$4 or opening) same (opaque or light\$6block\$4 or light\$4shield\$5 or non\$4transmis\$5 or non\$4transparen\$3 or chromium or Cr) same ((illuminat\$4 near6 source) or (light near6 source))) and ((interference near12 pattern))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
29	8	(illumination or light or radiation) and ((optic\$4 or project\$4 or object\$4) same lens\$4) and ((mask or reticle or photomask) same (mount or stage or hold\$4)) and (substrate or workpiece) and ((mask or reticle or photomask) same (slit\$4 or opening) same (opaque or light\$6block\$4 or light\$4shield\$5 or non\$4transmis\$5 or non\$4transparen\$3)) and ((interference near12 pattern)) and (pattern\$4 same slit same (contrast or distribut\$4 or (numerical near9 aperture))) and intensit\$4	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB